

EM Workflow Japan Liaison TF

Kyoichiro Asayama / JEOL Ltd.

Tsuyoshi Onishi / Hitachi High-Technologies Corporation

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Member

Leader

Kyoichiro Asayama (JEOL)

Tsuyoshi Ohnishi (HHT)

Tetsunori Murachi (Intel)

Hirokazu Tsunobuchi (KEYENCE)

Daisuke Sado (DAIHEN)

Hiroyuki Tanaka (HHT)

Mitsuhiro Matsuda (Hitachi Kokusai)

Tsuyoshi Nagashima (Miraial)

Tadamasa Tominaga (MURATA)

Kurio Fukushima (STEM)

Kenji Yamagata (DAIFUKU)

Yorinobu Kunimune (Renesas)

Kazuya Yamazaki (JEOL)

Supika Mashiro (TEL)

Toyoda (Hirata)

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Ballot Results (Doc.6311 letter ballot)

“SPECIFICATION FOR TEM LAMELLA CARRIERS USED IN ELECTRON MICROSCOPY WORKFLOWS”

Return($58/89 = 65.2\%$) : Accept(31), Reject(4), Abstain(23)

Negative comments

1. What is 'material'? If it means LC, replace 'material' with 'LC'. If it means the material of the LC, clarify the specific. As written, it's not consistent with the scope of the Standard.
2. 9.2 refers section 9 as the section that provides test method to certify the LC, but there is no test method in section 9 or any section in the Standard. Either remove 9.2, or provide test methods that can be used to certify the LC in this Standard.
3. According to this Letter Ballot, it is supposed to decide the location of the Lamella Carrier to write the ID mark. However, other specifications of ID mark should comply with ISO 29158.

Proposed corrected table including footnote

1. Adding footnote #3 on this title.
2. Delete 2-7.6 “Side Length of Square Dot” and 2-7.7 “Dot Depth”.
3. Align item numbers.

2-7. ID MARKING #3)				
	2-7.1	Type	2-dim square DMC	
	2-7.3 2	Position	Distance from Chord: 25 µm	by mutual agreement
♦	2-7.4 3	Face for ID Mark	(specify): Front Face [], Rear Face []	
	2-7.5 4	Dimensions of ID Mark Window	Width = 680 µm Height = 680 µm	by mutual agreement
♦	2-7.6	Side Length of Square Dot	(specify according to ISO 29158): Target [] ± Tolerance [] µm	by mutual agreement
♦	2-7.7	Dot Depth	(specify according to ISO 29158): Target [] ± Tolerance [] µm	by mutual agreement
♦	2-7.8 5	Content of ID Mark	(specify according to ISO 16022, ECC200): _____	

#1) Applies only to grid LC

#2) Applies only to half-moon LC

#3) ID marking are required to be written better than grade C of marking code quality refer to ISO 29158.

Alternative Proposal (2D ID code)

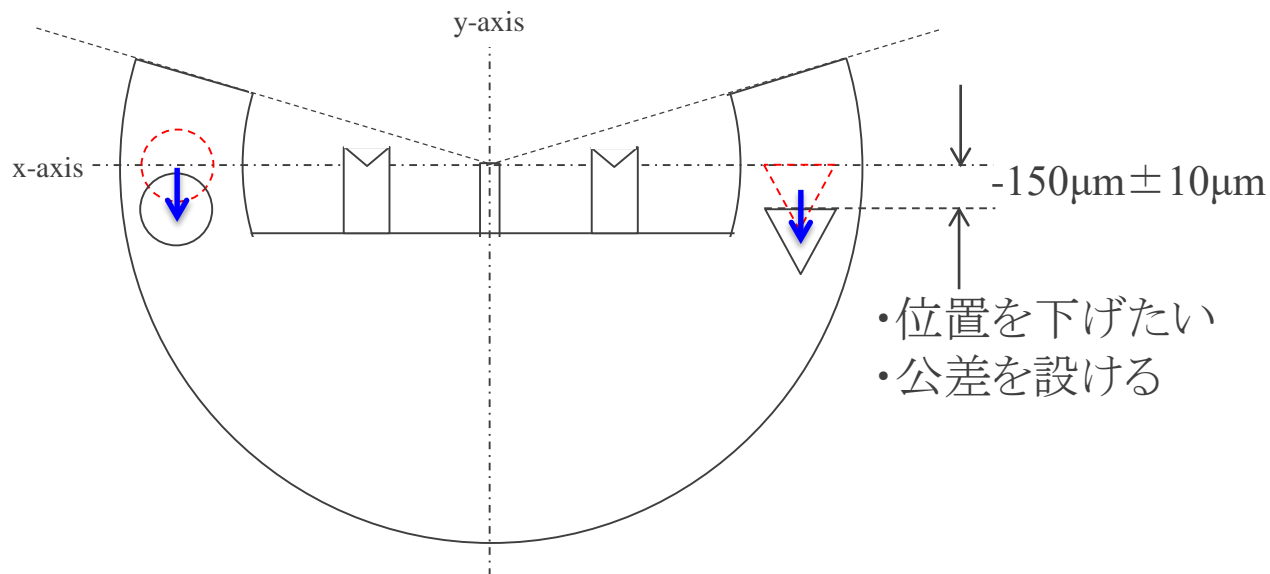
2-7. ID MARKING

	2-7.1	Type	2-dim square DMC	
	2-7.3	Position	Distance from Chord: 25 µm	by mutual agreement
♦	2-7.4	Face for ID Mark	(specify): Front Face [], Rear Face []	
	2-7.5	Dimensions of ID Mark Window	Width = 680 µm Height = 680 µm	by mutual agreement
♦	2-7.6	Side Length of Square Dot ^{#3,#4}	Target [] ± Tolerance [] µm	by mutual agreement
♦	2-7.7	Dot Depth ^{#3,#4}	Target [] ± Tolerance [] µm	by mutual agreement
♦	2-7.8	Marking Quality ^{#4}	Better than grade C according to ISO 29158	ISO 29158
♦	2-7.9	Content of ID Mark	(specify according to ISO 16022, ECC200): _____	

^{#3} Target values aiming at a Mark Grade better than C according to ISO 29158

^{#4} Specify either according to lines 2-7.6 and 2-7.7 or according to line 2-7.8

Fiducial Mark



◆	2-3.1	Center Fiducial ^{#1}	(specify): _____	
	2-3.2	Left Fiducial	Circle, Diameter $250 \pm 20 \mu\text{m}$, Center at $x = -1250 \pm 10 \mu\text{m}$ and $y = -150 \mu\text{m} \pm 10 \mu\text{m}$	by mutual agreement
	2-3.3	Right Fiducial	Triangle, Side Length $250 \pm 20 \mu\text{m}$, Basis Center at $x = 1250 \pm 10 \mu\text{m}$ and $y = -150 \mu\text{m} \pm 10 \mu\text{m}$ Corner Radius $\leq 30 \mu\text{m}$	by mutual agreement

PI & C TC (April. 3)

Ballot Results

<i>Document #</i>	<i>Document Title</i>	<i>Committee Action</i>	<i>A&R Forms for Approved Ballots</i>
6311	New Standard: Specification for TEM Lamella Carrier Used in Electron Microscopy Workflows	Failed	

Note 1: **Passed** ballots and line items will be submitted to the ISC Audit & Review Subcommittee for procedural review.

Note 2: **Failed** ballots and line items were returned to the originating task forces for re-work and re-balloting or abandoning.

Authorized Ballots

<i>#</i>	<i>When</i>	<i>TF</i>	<i>Details</i>
6311A	Cycle 5, 2019	Electron Microscopy Workflow TF	New Standard: Specification for TEM Lamella Carrier Used in Electron Microscopy Workflows

Schedule

- 4月27日 : Web meeting … (tentative)
- 5月12日 : cycle 5にBallot投入
- 5月26日～6月26日 : 投票期間
- 7月8日～11日 : SEMICON WEST期間中に審議

END

December 12, 2018

SEMI Japan
EMWF Liaison TF